

ABSTRACT

The present disclosure relates to a blank mask including: a transparent substrate; and a light shielding film disposed on the transparent substrate, wherein the light shielding film comprises a transition metal and at least one selected from the group consisting of oxygen and nitrogen, and wherein a Mtr value of Equation 1 below of a surface of the light shielding film is 6 or less:

[Equation 1]

$$Mtr = |Rsk| * Rku$$

where, in the Equation 1, $|Rsk|$ is an absolute value of an Rsk value, which is a height skewness of the surface of the light shielding film, and Rku is kurtosis of the surface of the light shielding film.

Figure 1